

Application No.: 10/673,347

Docket No.: 20140-00247-US1

AMENDMENTS TO THE CLAIMS

1. (Currently amended) A polish composition comprising abrasive particles and about 0.05 to about 5% by weight of a polyelectrolyte selected from the group consisting of an anionic polyelectrolyte or and a cationic polyelectrolyte, wherein the quantity of said anionic polyelectrolyte or cationic polyelectrolyte is in excess of the amount which adsorbs on the abrasive particles and is present in the composition as free or unabsorbed polyelectrolyte, and wherein the polyelectrolyte is an anionic polyelectrolyte where the polish composition is an selectively polishing silicon dioxide as compared to silicon nitride, or a cationic polyelectrolyte where the polish composition is for selectively polishing metals as compared to silicon dioxide, silicon nitride and/or silicon oxynitride.

2. (Original) The polish composition of claim 1 wherein the polyelectrolyte is a anionic polyelectrolyte.

3. (Original) The polish composition of claim 2 wherein the polyelectrolyte is a cationic electrolyte.

4. (Original) The polish composition of claim 1 wherein the polyelectrolyte has a molecular weight of less than about 100,000.

5. (Original) The polish composition of claim 1 wherein the polyelectrolyte has a molecular weight of about 300 to about 20,000.

6. (Original) The polish composition of claim 1 wherein the polyelectrolyte is selected from the group consisting of poly (acrylic acid), poly (methacrylic acid), poly (methyl methacrylic acid), poly (maleic acid), and poly (vinylsulfonic acid).

7. (Original) The polish composition of claim 1 wherein the polyelectrolyte is selected from the group consisting of poly (vinylamine), poly (ethylenimine) and poly (4-vinylpyridine).

8. (Original) The polish composition of claim 1 wherein the polyelectrolyte is poly (acrylic acid).

9. (Original) The polish composition of claim 1 wherein the polyelectrolyte is polyethylenimine.

10. (Original) The polish composition of claim 1 wherein the abrasive particles comprise a member selected from the group consisting of ceria, alumina, silica and zirconia.

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11. (Original) The polish composition of claim 1 wherein the amount of the abrasive particles is about 0.1 to about 20 percent by weight.

12. (Original) The polish composition of claim 1 being aqueous slurry.

13-21. (Canceled)

22. (New) The polish composition of claim 12 wherein the amount of polyelectrolyte is about 0.3 to about 1 percent by weight.

23. (New) The polish composition of claim 1 wherein the amount of polyelectrolyte is about 0.3 to about 1 percent by weight.

24. (New) The polish composition of claim 23 wherein the amount of abrasive particles is about 0.3 to about 2 percent by weight.

25. (New) The polish composition of claim 1 wherein the amount of abrasive particles is about 0.3 to about 2 percent by weight.